Electronic Supplementary Material (ESI) for Nanoscale.

Supplementary Information

Spinodal Decomposition Introduces Strain-Enhanced Thermochromism in Polycrystalline $V_{1-x}Ti_xO_2$ Thin Films

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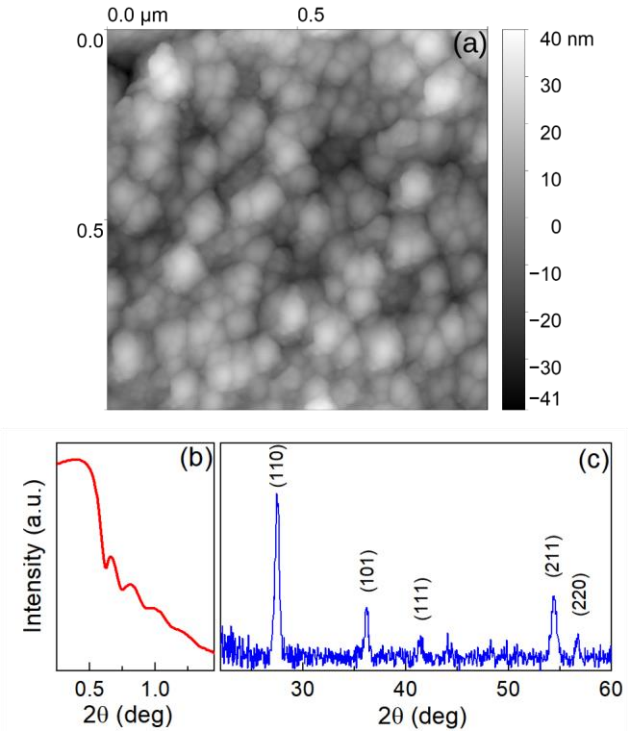

Figure S1 Characterization of TiO_2 films grown on fused quartz substrates under growth conditions optimized for pure-phase VO_2 synthesis. (a) AFM images of the TiO_2 surface. (b) XRR oscillations for TiO_2 film with a thickness of 34 nm. (c) XRD pattern of the TiO_2 film shown in (b).

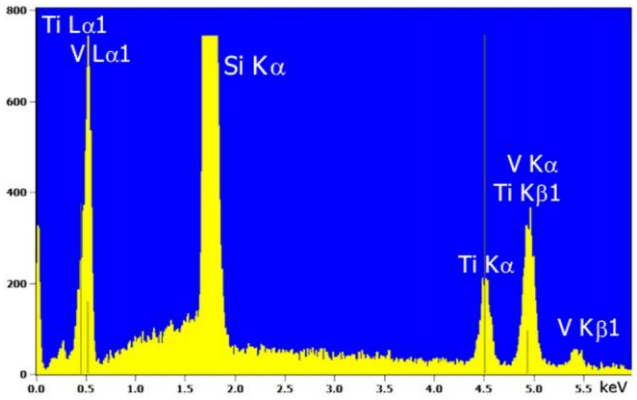

Figure S2 EDX spectrum of the 180-nm-thick $V_{1-x}Ti_xO_2$ film grown on a fused quartz substrate with a calculated metal composition corresponding to x=0.34.

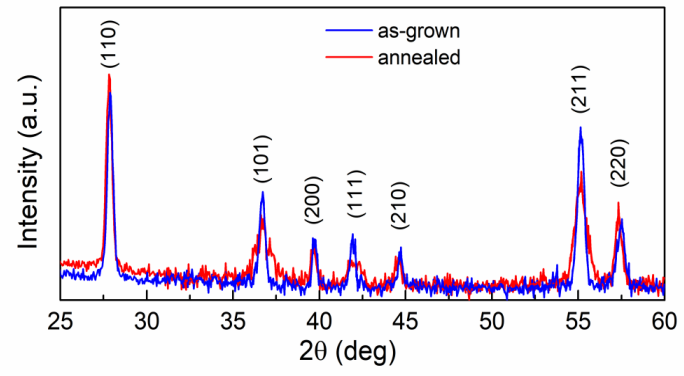

Figure S3 XRD patterns of $V_{0.65}Ti_{0.35}O_2$ film grown on fused quartz substrate before and after annealing at 530 °C for 1 hour.